

7th EUV-FEL Workshop

30, January 2023

1:00PM-5:40PM (JST)

Timetable/Program

Subject	Presentation time (minutes)	JST (UTC + 9) Japan Time	CST (UTC+8) China Time	CET (UTC + 1) Central Europe Time	PST(UTC - 8) California Time	Title	Presenter	Affiliation	Chair
		30/Jan./2023	30/Jan./2023	30/Jan./2023	29/Jan./2023				
Opening remarks	5	13:00-13:05	12:00-12:05	05:00-05:05	20:00-20:05	Opening remarks	Sunao Ishihara	Representative of EUV-FEL Light Source Study Group for Industrialization	Hiroshi Kawata
Target of the workshop	5	13:05-13:10	12:05-12:10	05:05-05:10	20:05-20:10	Target of the workshop	Hiroshi Kawata	KEK (Secretary of the Workshop)	
Key note lecture	45	13:10-13:55	12:10-12:55	05:10-05:55	20:10-20:55	Free-electron lasers and the future of EUV lithography	Harry J. Levinson	HJL Lithography	Akiyoshi Suzuki
Invited speaker (1)	35	13:55-14:30	12:55-13:30	05:55-06:30	20:55-21:30	Technical issue of EUVL and prospect for EUVL and Beyond EUVL	Takeo Watanabe	University of Hyogo	
Break	15	14:30-14:45	13:30-13:45	06:30-06:45	21:30-21:45				
Invited speaker (2)	35	14:45-15:20	13:45-14:20	06:45-07:20	21:45-22:20	Present state of the EUV-FEL light source for future lithography	Norio Nakamura	KEK	Shigemi Sasaki
Invited speaker (3)	35	15:20-15:55	14:20-14:55	07:20-07:55	22:20-22:55	Current status and prospect of extreme ultraviolet resists	Takahiro Kozawa	Osaka University	Shinji Okazaki
Invited speaker (4)	35	15:55-16:30	14:55-15:30	07:55-08:30	22:55-23:30	TEL's Patterning Approaches Toward High NA EUV Lithography	Seiji Nagahara	Tokyo Electron Ltd.	
Closing address & Photo-session	10	16:30-16:40	15:30-15:40	08:30-08:40	23:30-23:40	Closing address	Shin-ichi Adachi	KEK	Hiroshi Kawata
Site tour (cERL & STF)	60	16:40-17:40							